



## The gate modulation of channel conductance of $MoS_2$ field effect transistor using 2D ferroelectric CuInP<sub>2</sub>S<sub>6</sub>

## Abstract

This study examined the gating effect of two dimensional (2D) van der Waals (vdW) ferroelectrics CuInP<sub>2</sub>S<sub>6</sub> (CIPS) in modulation of channel current of 2D semiconductor MoS<sub>2</sub> field effect transistor (FET). Recently, ferroelectricity has been discovered in 2D vdW materials, such as SnTe, In<sub>2</sub>Se<sub>3</sub>, and CIPS. These materials can potentially preserve ferroelectricity in the monoatomic layer limit, making them promising for developing ferroelectric-based 2D nanoelectronics.

In this study, we explored the gating effect on 2D  $MoS_2$  FET top gated by 2D vdW ferroelectrics CIPS. The polarizations of CIPS on different base layers are robust after domain writing using conductive atomic force microscopy (AFM). The channel conductance has been sufficiently suppressed after transferring the CIPS top gate on MoS<sub>2</sub>, which is due to the charge carrier depletion induced by the polarization of as-grown CIPS. We also use piezoresponse force microscopy (PFM) to switch the polarization of the CIPS top gate into the  $P_{up}$  and  $P_{down}$ states, which can induce non-volatile modulation of channel current and achieve a very large current on/off ratio of around 10<sup>7</sup>. Our research can provide important material parameters for designing CIPS-based nanoelectronic devices, paving the path for their implementation in programmable, flexible nonvolatile memory, neuromorphic computing, and optoelectronic applications.

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